

Date :- 17.1.2013

Subject :- Modified specification of Reactive Magnetron Sputtering System for ZnO film deposition in Pre-Bid Conference.

Reference:- Open/Global Tender No. 602/P-50/SNTG/10-Pur/2012/T-109 dated 21.12.2012.

1. Rough vacuum pump Oerlikon Leybold should be in technical specification 3.1.
2. Power sources RF-7 and SEREN should be included in technical specification 4.1.
3. Temperature uniformity should be $\pm 1\%$ in place of $\pm 1^{\circ}\text{C}$ in technical specification 6.2.
4. Vendor will demonstrate the capability of same machine for ZnO film deposition as described in technical specification 2, specification should be added in point number 10.1.
5. The specification 6.1 should be replaced as "Controlled heating from room temperature to 600°C and controlled cooling from process temperature. The temperature stability should be $\pm 1^{\circ}\text{C}$ or better."